



# BENEQ Transform<sup>®</sup> platform

## BENEQ set to Transform<sup>®</sup> the More-than-Moore Era

Beneq Transform<sup>®</sup> establishes a completely new class of ALD cluster tool products in its versatility and adaptability to address a broad range of applications and market segments. Beneq Transform<sup>®</sup> provides winning ALD solutions for the More-than-Moore market.

## Beneq ALD Solutions for More-than-Moore Markets

### CMOS IMAGE SENSORS

- BSI CIS, Novel CIS design, & Lens module

### μOLED

### LED, μLED, DETECTORS & PHOTONICS

- VCSEL & Optoelectronic ICs

### RF FILTERS & ICs

- TC-SAW, SW & TF-SAW filters
- BAW (SMR & FBAR) filters

### MEMS, SENSORS & ACTUATORS

- Inkjet heads
- Biochips & Microfluidics
- Piezo actuators
- Inertial & Pressure sensors

### POWER DEVICES

- Trench, SJ & SiC trench MOSFET
- IGBT
- GaN HEMT & Vertical GaN

### ADVANCED PACKAGING

**VERSATILITY:** Combines thermal and plasma-enhanced ALD processing modules for single wafer or batch

**PRODUCTIVITY:** Unique pre-heating module boosts productivity by eliminating waiting time

**FAB-READY:** Industry-standard horizontal single-wafer automation for wafer sizes from 75 mm to 200 mm, SEMI S2/S8 certified, SECS/GEM ready

**SERVICEABILITY:** Easy access for rapid maintenance

**AVAILABLE PROCESSES:** Al<sub>2</sub>O<sub>3</sub>, SiO<sub>2</sub>, HfO<sub>2</sub>, Ta<sub>2</sub>O<sub>5</sub>, TiO<sub>2</sub>, TiN, AlN, SiN<sub>x</sub>, ZnO, ZrO, down to <1 % 1σ thickness non-uniformity in batch (Al<sub>2</sub>O<sub>3</sub> @300 °C, WiW, WtW, BtB)





# BENEQ Transform<sup>®</sup> and Transform<sup>®</sup> Lite

## Beneq Transform<sup>®</sup> is a winning solution

### Productivity & Performance

- Beneq Transform<sup>®</sup> provides best productivity and performance at the lowest cost per wafer

### Reliability

- Superior reactor design for reliable operation and high uptime

### Serviceability

- Easy access for rapid maintenance is central to platform design

### Versatility

- One platform to serve multiple applications and capacity needs
- Thermal batch and PEALD integrated on the same platform

### Flexibility

- Configure to current needs, retrofit modules, size conversion 75 to 200 mm
- Roadmap being deployed for 300 mm and innovative ALD technologies

	Transform <sup>®</sup>	Transform <sup>®</sup> Lite
MAXIMUM CONFIGURATION	3 ALD modules + pre-heater	2 ALD modules + pre-heater
TRANSFER MODULE	Brooks Mx600SS	Brooks Mx400
COOLING OPTION	Built-in	Facet-mounted
VCE LOADLOCKS	2	1
SUBSTRATE SIZE	75, 100, 150 or 200 mm	75, 100, 150 or 200 mm
MAXIMUM DIMENSIONS	3120x4070x2140 mm	3060x3340x2140 mm
INTEGRATION	SECS/GEM	SECS/GEM
THROUGHPUT EXAMPLE 50NM AL2O3 300 °C	15 wafers/hour (1PM) > 40 wafers/hour (3PM's)	15 wafers/hour (1PM) >25 wafers/hour (2PM's)

### FIELD SERVICE ADVANTAGE

Beneq's service advantage includes rapid response with local personnel

